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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/590,046	06/15/2007	Taku Hirayama	SHIGA7.055APC	5635
20995 7590 03/17/2010 KNOBBE MARTENS OLSON & BEAR LLP 2040 MAIN STREET			EXAMINER	
			JOHNSON, CONNIE P	
FOURTEENTH FLOOR IRVINE, CA 92614		ART UNIT	PAPER NUMBER	
			1795	
			NOTIFICATION DATE	DELIVERY MODE
			03/17/2010	ELECTRONIC

Please find below and/or attached an Office communication concerning this application or proceeding.

The time period for reply, if any, is set in the attached communication.

Notice of the Office communication was sent electronically on above-indicated "Notification Date" to the following e-mail address(es):

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	Application No.	Applicant(s)
	10/590,046	HIRAYAMA ET AL.
Office Action Summary	Examiner	Art Unit
	CONNIE P. JOHNSON	1795
The MAILING DATE of this communication ap Period for Reply	pears on the cover sheet with the	correspondence address
A SHORTENED STATUTORY PERIOD FOR REPL WHICHEVER IS LONGER, FROM THE MAILING D. - Extensions of time may be available under the provisions of 37 CFR 1. after SIX (6) MONTHS from the mailing date of this communication. - If NO period for reply is specified above, the maximum statutory period Failure to reply within the set or extended period for reply will, by statut Any reply received by the Office later than three months after the mailing earned patent term adjustment. See 37 CFR 1.704(b).	DATE OF THIS COMMUNICATIO .136(a). In no event, however, may a reply be I will apply and will expire SIX (6) MONTHS fro te, cause the application to become ABANDON	DN. timely filed m the mailing date of this communication. IED (35 U.S.C. § 133).
Status		
1) ☐ Responsive to communication(s) filed on 17 L 2a) ☐ This action is FINAL . 2b) ☐ This 3) ☐ Since this application is in condition for allowed closed in accordance with the practice under	is action is non-final. ance except for formal matters, p	
Disposition of Claims		
4) ☐ Claim(s) 1-20 is/are pending in the application 4a) Of the above claim(s) is/are withdra 5) ☐ Claim(s) is/are allowed. 6) ☐ Claim(s) 1-20 is/are rejected. 7) ☐ Claim(s) is/are objected to. 8) ☐ Claim(s) are subject to restriction and/o	awn from consideration.	
9)☐ The specification is objected to by the Examination The drawing(s) filed on is/are: a)☐ acceptable.	cepted or b) objected to by the	
Applicant may not request that any objection to the Replacement drawing sheet(s) including the correct 11) The oath or declaration is objected to by the E	ction is required if the drawing(s) is c	bjected to. See 37 CFR 1.121(d).
Priority under 35 U.S.C. § 119		
12) Acknowledgment is made of a claim for foreign a) All b) Some * c) None of: 1. Certified copies of the priority document 2. Certified copies of the priority document 3. Copies of the certified copies of the priority document application from the International Bureat * See the attached detailed Office action for a list	nts have been received. nts have been received in Applica prity documents have been recein au (PCT Rule 17.2(a)).	ntion No ved in this National Stage
Attachment(s) 1) Notice of References Cited (PTO-892) 2) Notice of Draftsperson's Patent Drawing Review (PTO-948) 3) Information Disclosure Statement(s) (PTO/SB/08) Paper No(s)/Mail Date	4) Interview Summa Paper No(s)/Mail 5) Notice of Informal 6) Other:	Date

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DETAILED ACTION

Response to Amendment

1. The remarks and amendment filed 12/17/2009 are entered and fully considered.

- 2. Claims 1-20 are presented.
- 3. Claim 20 is new.

Double Patenting

4. The nonstatutory double patenting rejection is based on a judicially created doctrine grounded in public policy (a policy reflected in the statute) so as to prevent the unjustified or improper timewise extension of the "right to exclude" granted by a patent and to prevent possible harassment by multiple assignees. A nonstatutory obviousness-type double patenting rejection is appropriate where the conflicting claims are not identical, but at least one examined application claim is not patentably distinct from the reference claim(s) because the examined application claim is either anticipated by, or would have been obvious over, the reference claim(s). See, e.g., *In re Berg*, 140 F.3d 1428, 46 USPQ2d 1226 (Fed. Cir. 1998); *In re Goodman*, 11 F.3d 1046, 29 USPQ2d 2010 (Fed. Cir. 1993); *In re Longi*, 759 F.2d 887, 225 USPQ 645 (Fed. Cir. 1985); *In re Van Ornum*, 686 F.2d 937, 214 USPQ 761 (CCPA 1982); *In re Vogel*, 422 F.2d 438, 164 USPQ 619 (CCPA 1970); and *In re Thorington*, 418 F.2d 528, 163 USPQ 644 (CCPA 1969).

A timely filed terminal disclaimer in compliance with 37 CFR 1.321(c) or 1.321(d) may be used to overcome an actual or provisional rejection based on a nonstatutory double patenting ground provided the conflicting application or patent either is shown to be commonly owned with this application, or claims an invention made as a result of activities undertaken within the scope of a joint research agreement.

Effective January 1, 1994, a registered attorney or agent of record may sign a terminal disclaimer. A terminal disclaimer signed by the assignee must fully comply with 37 CFR 3.73(b).

5. Claims 1-5, 8-13 and 16-20 are provisionally rejected on the ground of nonstatutory obviousness-type double patenting as being unpatentable over claims 1, 3-5 and 7 of copending Application No. 11/572,630. Although the conflicting claims are not identical, they are not patentably distinct from each other because the copending application discloses a positive resist composition comprising a base material for a

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pattern-forming material which contains a protector (XI) of a polyhydric phenol compound (x) having two or more phenolic hydroxyl groups and a photoacid generator.

This is a <u>provisional</u> obviousness-type double patenting rejection because the conflicting claims have not in fact been patented.

- 6. Claims 1-5, 8-13 and 16-20 are rejected on the ground of nonstatutory obviousness-type double patenting as being unpatentable over claims 1, 2 and 5 of U.S. Patent No. 7,504,196 B2. Although the conflicting claims are not identical, they are not patentably distinct from each other because the patent discloses a positive resist composition comprising a base material with the structure of formula (I) in present claim 1, an acid generator and a nitrogen-containing compound.
- 7. Claims 1-5, 8-13 and 16-20 are provisionally rejected on the ground of nonstatutory obviousness-type double patenting as being unpatentable over claims 4-7 of copending Application No. 11/917,458. Although the conflicting claims are not identical, they are not patentably distinct from each other because the copending application discloses a positive resist composition comprising a base material with the structure of formula (I) in present claim 1, an acid generator and a nitrogen-containing compound.

This is a <u>provisional</u> obviousness-type double patenting rejection because the conflicting claims have not in fact been patented.

8. Claims 1-5, 8-13 and 16-20 are provisionally rejected on the ground of nonstatutory obviousness-type double patenting as being unpatentable over claims 1, 6 and 9 of copending Application No. 11/574,805. Although the conflicting claims are not identical, they are not patentably distinct from each other because the copending

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application discloses a resist composition comprising a base material with aciddissociable, dissolution-inhibiting groups, an acid generator and a nitrogen-containing compound.

This is a <u>provisional</u> obviousness-type double patenting rejection because the conflicting claims have not in fact been patented.

9. Claims 1-5, 8-13 and 16-20 are provisionally rejected on the ground of nonstatutory obviousness-type double patenting as being unpatentable over claims 1 and 2 of copending Application No. 11/813,511. Although the conflicting claims are not identical, they are not patentably distinct from each other because the copending application discloses a resist composition comprising a polyhydric phenol compound with acid-dissociable, dissolution-inhibiting groups with a molecular weight of 300 to 2500, an acid generator and a nitrogen-containing compound. Although not exemplified in the claims, it would have been obvious to one of ordinary skill in the art that the polyhydric phenol compound is present in the amount as claimed based the components in table 1, page 13.

This is a <u>provisional</u> obviousness-type double patenting rejection because the conflicting claims have not in fact been patented.

10. Claims 1-5, 8-13 and 16-20 are provisionally rejected on the ground of nonstatutory obviousness-type double patenting as being unpatentable over claims 1-6 of copending Application No. 11/914,451. Although the conflicting claims are not identical, they are not patentably distinct from each other because the copending application discloses a resist composition comprising a polyhydric phenol compound with acid-dissociable, dissolution-inhibiting groups with a molecular weight of 300 to

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2500, an acid generator and a nitrogen-containing compound. Although not exemplified in the claims, it would have been obvious to one of ordinary skill in the art that the polyhydric phenol compound is present in the amount as claimed based the components in table 4, page 20.

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This is a <u>provisional</u> obviousness-type double patenting rejection because the conflicting claims have not in fact been patented.

- 11. Claims 1-5, 8-13 and 16-20 are provisionally rejected on the ground of nonstatutory obviousness-type double patenting as being unpatentable over claims 1, 2, 3, 5 and 6 of copending Application No. 11/718,091. Although the conflicting claims are not identical, they are not patentably distinct from each other because the copending application discloses a resist composition comprising a base material with aciddissociable, dissolution-inhibiting groups with a molecular weight of 300 to 2500, an acid generator and a nitrogen-containing compound. Although not exemplified in the claims, it would have been obvious to one of ordinary skill in the art that the polyhydric phenol compound is present in an amount as claimed because the reference teaches the polyhydric phenol is present in an amount of preferably 100% by mass (page 8, [0083]). This is a <u>provisional</u> obviousness-type double patenting rejection because the conflicting claims have not in fact been patented.
- Claims 1-5, 8-13 and 16-20 are provisionally rejected on the ground of 12. nonstatutory obviousness-type double patenting as being unpatentable over claims 1-7 of copending Application No. 11/994,602. Although the conflicting claims are not identical, they are not patentably distinct from each other because the copending application discloses a resist composition comprising a base material with acid-

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dissociable, dissolution-inhibiting groups with a molecular weight of 300 to 2500, an acid generator and a nitrogen-containing compound. Although not exemplified in the claims, it would have been obvious to one of ordinary skill in the art that the polyhydric phenol compound is present in an amount as claimed based on the components in table 3 (page 19).

This is a <u>provisional</u> obviousness-type double patenting rejection because the conflicting claims have not in fact been patented.

Response to Arguments

Applicant's arguments filed 12/17/2009, with respect to the rejection(s) of claim(s) 1, 3, 5, 8, 9, 11, 13 and 16-19 under 102(b) and claims 1, 2, 4, 10 and 12 under 103(a) have been fully considered and are persuasive. Therefore, the rejection has been withdrawn. However, upon further consideration, a new ground(s) of rejection is made herein.

Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to CONNIE P. JOHNSON whose telephone number is (571)272-7758. The examiner can normally be reached on 7:30am-4:00pm Monday thru Friday.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Cynthia Kelly can be reached on 571-272-1526. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

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Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free). If you would like assistance from a USPTO Customer Service Representative or access to the automated information system, call 800-786-9199 (IN USA OR CANADA) or 571-272-1000.

/Connie P. Johnson/ Examiner, Art Unit 1795 Page 7

/Cynthia H Kelly/

Supervisory Patent Examiner, Art Unit 1795